

	Type	L #	Hits	Search Text	DBs	Time Stamp	Error Count in Definitions
1	BRS	L1	4032	iminodiacetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:29	0
2	BRS	L2	38	1 and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 14:40	0
3	BRS	L3	236	(thioester or thioether or carbothiolic or carbothionic or thiocarboxylic or tihisalicylic) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:35	0
4	BRS	L4	12	3 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:42	0
5	BRS	L5	41	((organic and inorganic) with (medium or media)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:43	0
6	BRS	L6	3	5 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:45	0
7	BRS	L7	3	((nonaqueous) with (medium or media)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:10	0
8	BRS	L8	66	(nonaqueous) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 13:45	0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Error Count	Detail	Errors
9	BRS	L9	9	8 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 14:41			0
10	BRS	L10	1270	("pad" with (nonabrasive or fixed)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:27			0
11	BRS	L11	723	("pad" with (nonabrasive or fixed)) same (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 14:41			0
12	BRS	L12	174	11 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:17			0
13	BRS	L13	2	((nonaqueous) with (slurry)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:13			0
14	BRS	L14	33	((nonaqueous) with (solvent)) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:17			0
15	BRS	L15	400	(DMSO) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:17			0
16	BRS	L16	23	15 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:56			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Error Count	Message Detail	Error Initiation
17	BRS	L17	2514	(alcohol or ketone) and (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:27	0		
18	BRS	L18	280	(alcohol or ketone) same (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:27	0		
19	BRS	L19	100	(alcohol or ketone) with (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:55	0		
20	BRS	L20	126	(carrier with (water or nonaqueous or organic or ketone or alcohol)) same(CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:58	0		
21	BRS	L21	48	(carrier with (water or nonaqueous or organic or ketone or alcohol)) with (CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:56	0		
22	BRS	L22	18	21 and 438/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:57	0		
23	BRS	L23	12	(carrier with (nonaqueous or organic or ketone or alcohol)) same(CMP or "chemical mechanical polishing")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/09/06 15:58	0		